

Notice of References Cited	Application/Control No. 10/689,855	Applicant(s)/Patent Under Reexamination SHIGETA ET AL.	
	Examiner Mike Qi	Art Unit 2871	Page 1 of 1

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	C	US-5,493,426	02-1996	Johnson et al	359/40
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	E	US-6,791,648 B2	09-2004	Tanaka et al	349/129
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Lu et al., "29.4: Homeotropic Alignment by Single Oblique Evaporation of SiO ₂ and Its Application to High resolution Microdisplays" SID 00 DIGEST, pp.446-449,2000
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.